

[10191/3399]

**REPLY UNDER 37 C.F.R. § 1.116
EXPEDITED PROCEDURE
GROUP ART UNIT 1765**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

10 NN ENTER

Appl. No.	:	10/691,108	Confirmation No. 4772	LV
Applicant	:	Klaus BREITSCHWERDT		
Filed	:	October 22, 2003		
Title	:	DEVICE AND METHOD FOR ANISOTROPIC PLASMA ETCHING OF A SUBSTRATE, PARTICULARLY A SILICON ELEMENT		
TC/A.U.	:	1765		
Examiner	:	Lan Vinh		

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY UNDER 37 C.F.R. § 1.116

Sir:

In response to the Final Office Action of August 8, 2006, please amend the above-captioned application without prejudice as follows.

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper

Remarks begin on page 4 of this paper.